

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Enomoto, et al.

Serial No.: 09/019,087

Filed: 02/05/98

Title: Manufacturing Method of Semiconductor IC Device



Docket No.: TIJ-24816

Art Unit: 1765

Examiner: Perez-Ramos, 

TECHNOLOGY CENTER 1700

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AMENDMENT UNDER 37 CFR 1.115

Assistant Commissioner for Patents
Box Non-fee Amendments
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William B. Kempster, Reg. No. 28,228

November 6, 2000
Date

Sir:

In response to the Office Action dated July 5, 2000 in the above-identified patent application. They are respectfully submitted as a full and complete response to that Action.

REMARKS

Reconsideration of the application in view of the followings remarks is respectfully requested.

The Examiner rejects Claims 1-11 under 35 U.S.C. § 103(a), as being unpatentable over Tsuji '625 in view of Harari '739. This rejection is respectfully traversed.

The Examiner states that Tsuji teaches the forming of a first mask film on an insulating film as shown in column 5, line 24 of the reference. This is incorrect. This portion of Tsuji refers to Figures 2A and 2B. As is clear from Figure 2B, the first mask **23** recited on lines 24-25 of column 5, are on a reticule which is used to expose the photosensitive agent on the semiconductor device itself. This is not only clear from the drawing which shows the reticule above the semiconductor device, but also clear from the fact that on lines 22-23, it recites the use of a **g** ray stepper for the first exposure. As is known to those skilled in the art, a stepper is